



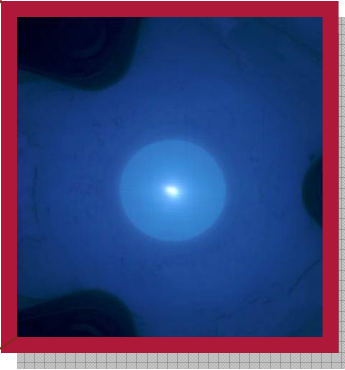
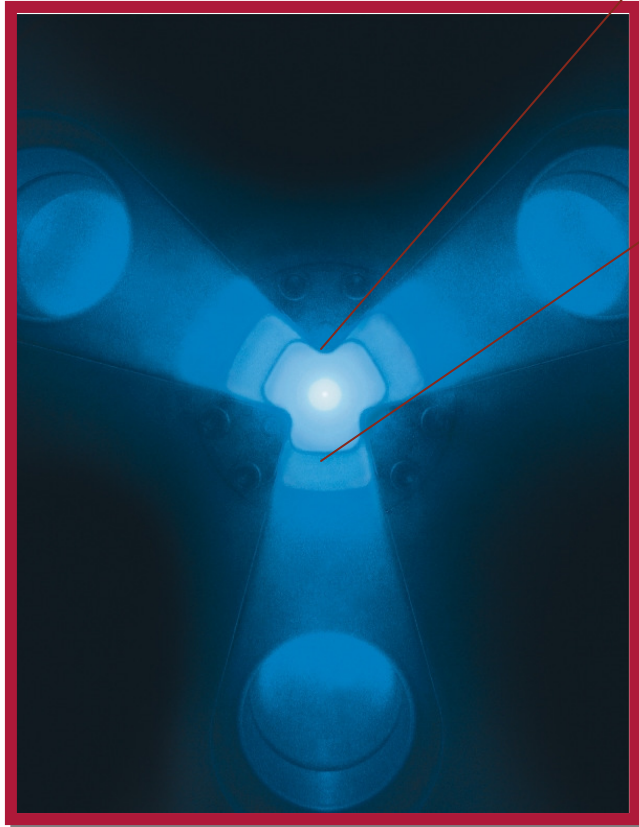
EQ-10 EUV Source for Metrology Applications

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Key Requirements for a Metrology Source

- High Brightness
- Excellent Spatial Stability
- High Pulse-Pulse Stability
- High System Reliability

EQ-10 Source

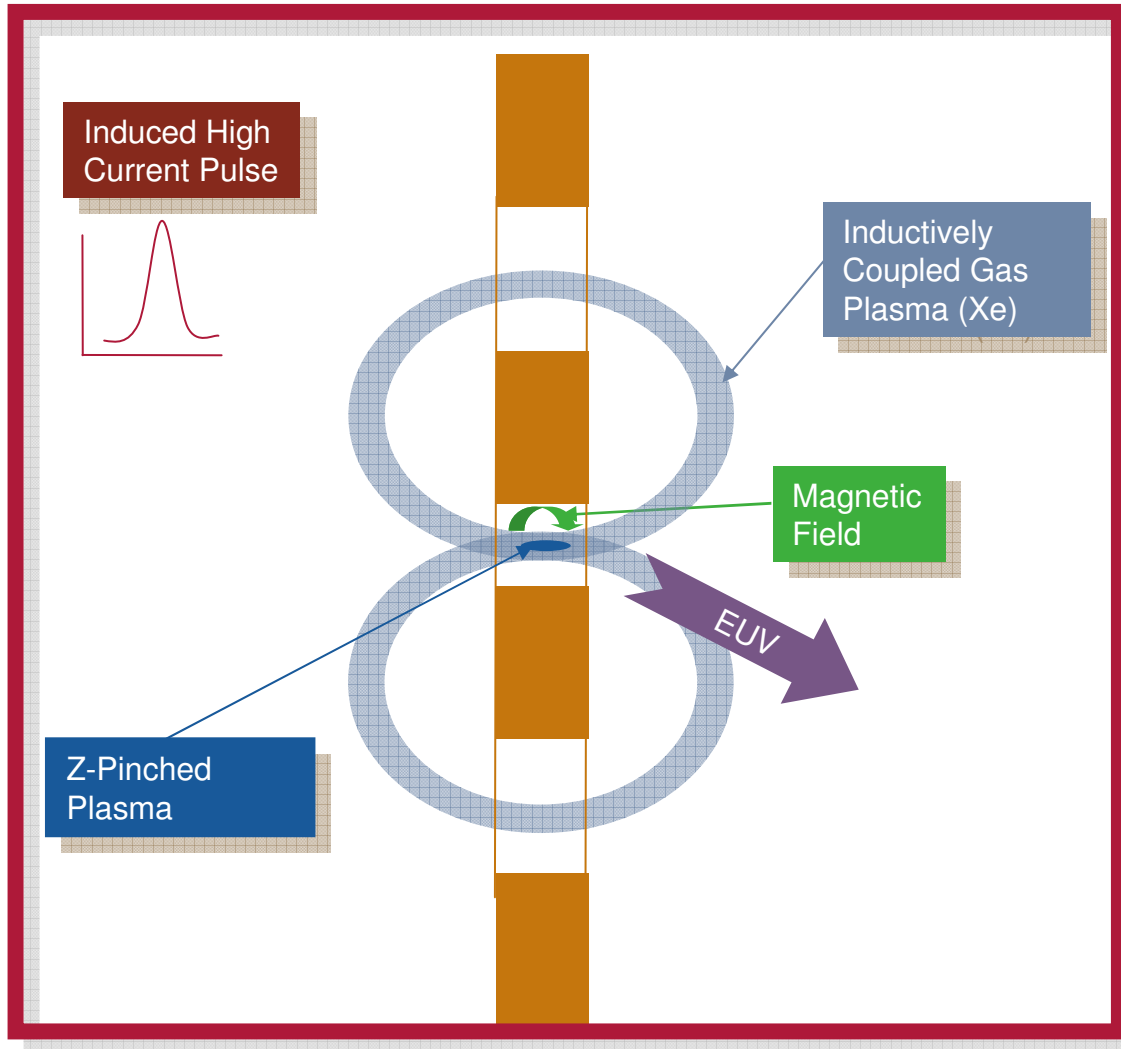


- Introduced in 2005
- 13.5nm $\pm 1\%$ Power in 2 π
 - 10W continuously
 - Now 20W
 - @2 kHz
- 10kHz operation also
- Operates continuously for days and weeks



Electrodeless Z-Pinch

ENERGETIQ



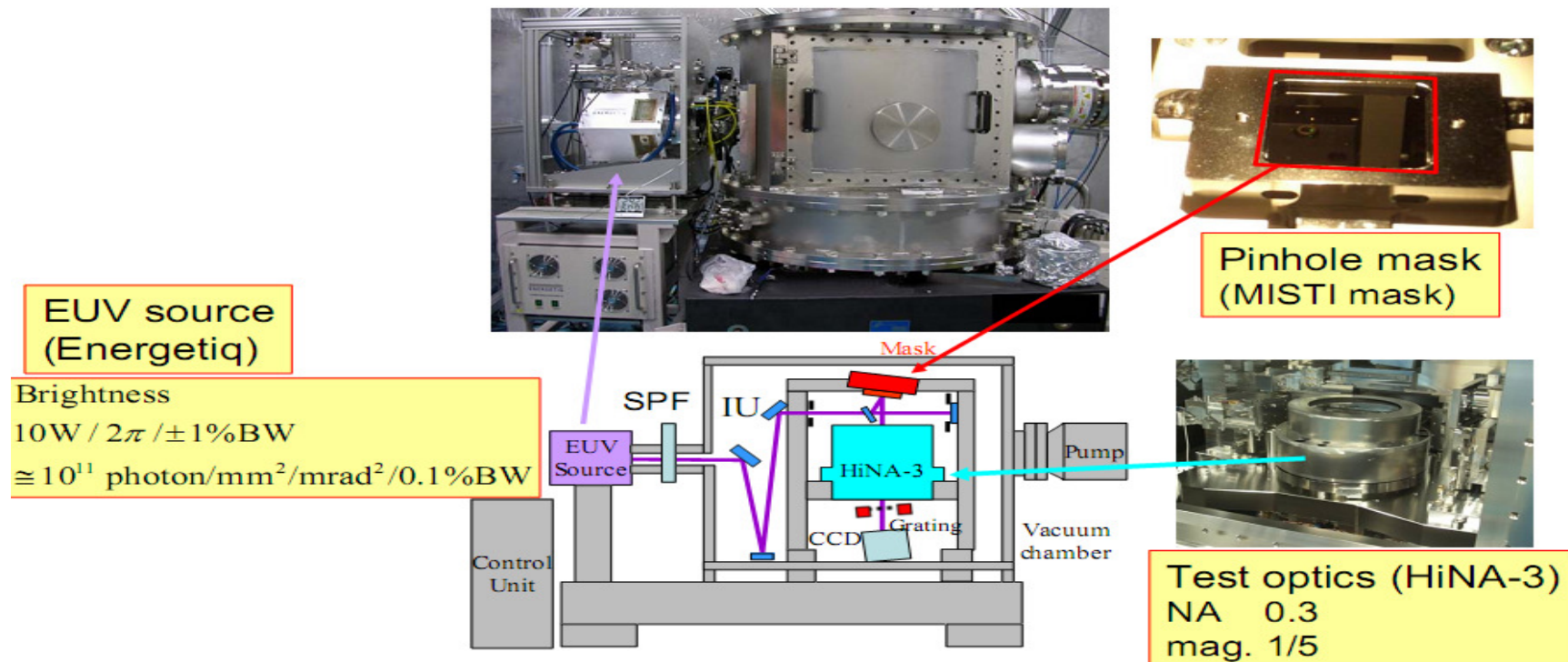
- Inductive design eliminates electrodes and electrode current
- Plasma is magnetically confined away from source components and 'pinned' electromagnetically to the geometric center of the bore

System Reliability

- Shipped over 15 sources in the field
- Installations in Japan, Europe and US
- Systems being operated 24/7 with minimal downtime
 - One system has many 10s of billions of pulses at 2kHz at 24/7 operation
- Systems integrated into tools for research and development
 - Actinic Inspection
 - Resist Outgassing
 - Mask Contamination
 - Optics Testing

Wavefront Metrology Tool Optics Testing

MISTI experimental setup



Actinic Mask Defect Detection Tool at MIRAI-Selete

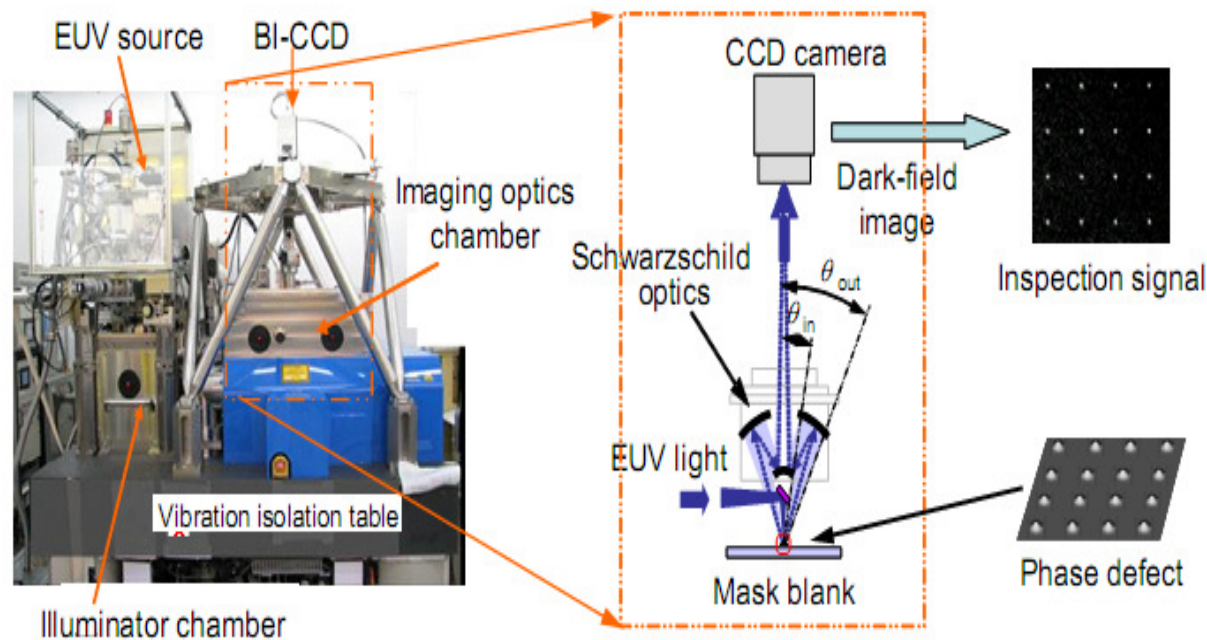
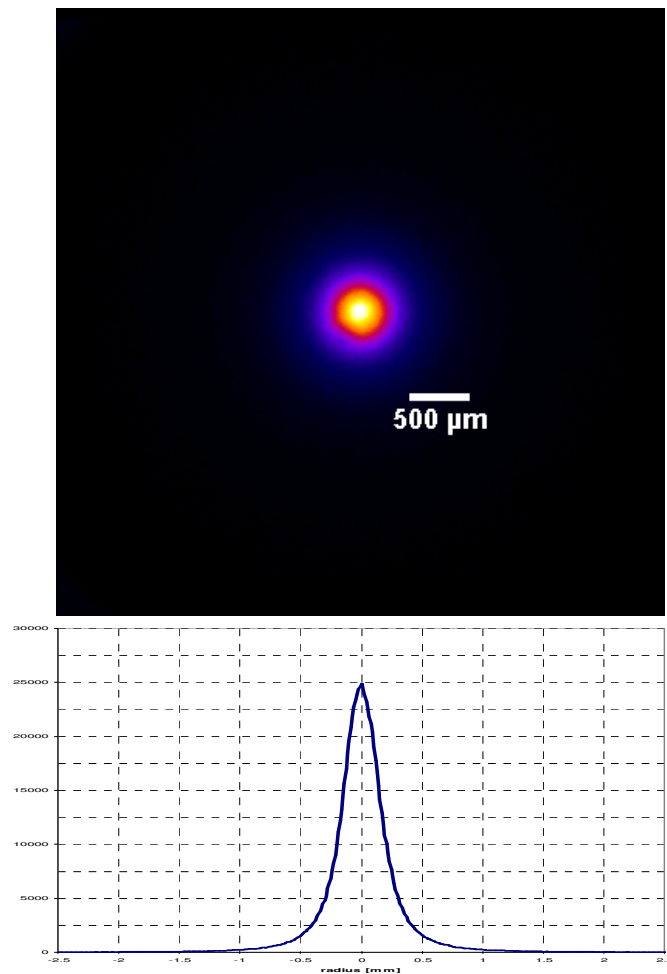


Figure 2 Actinic mask blank inspection tool built at MIRAI-Selete clean room and concept of its inspection optics using dark-field imaging.

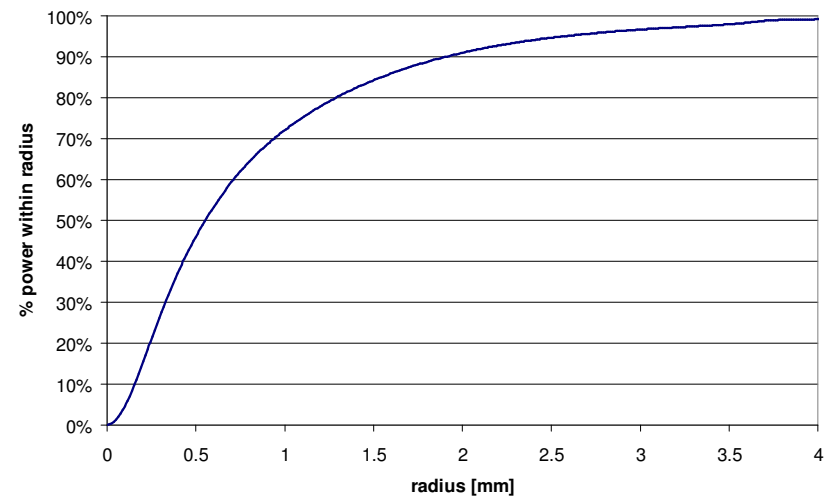


Recent Improvements in EQ-10 Brightness and Power

EQ-10 in-band EUV Brightness

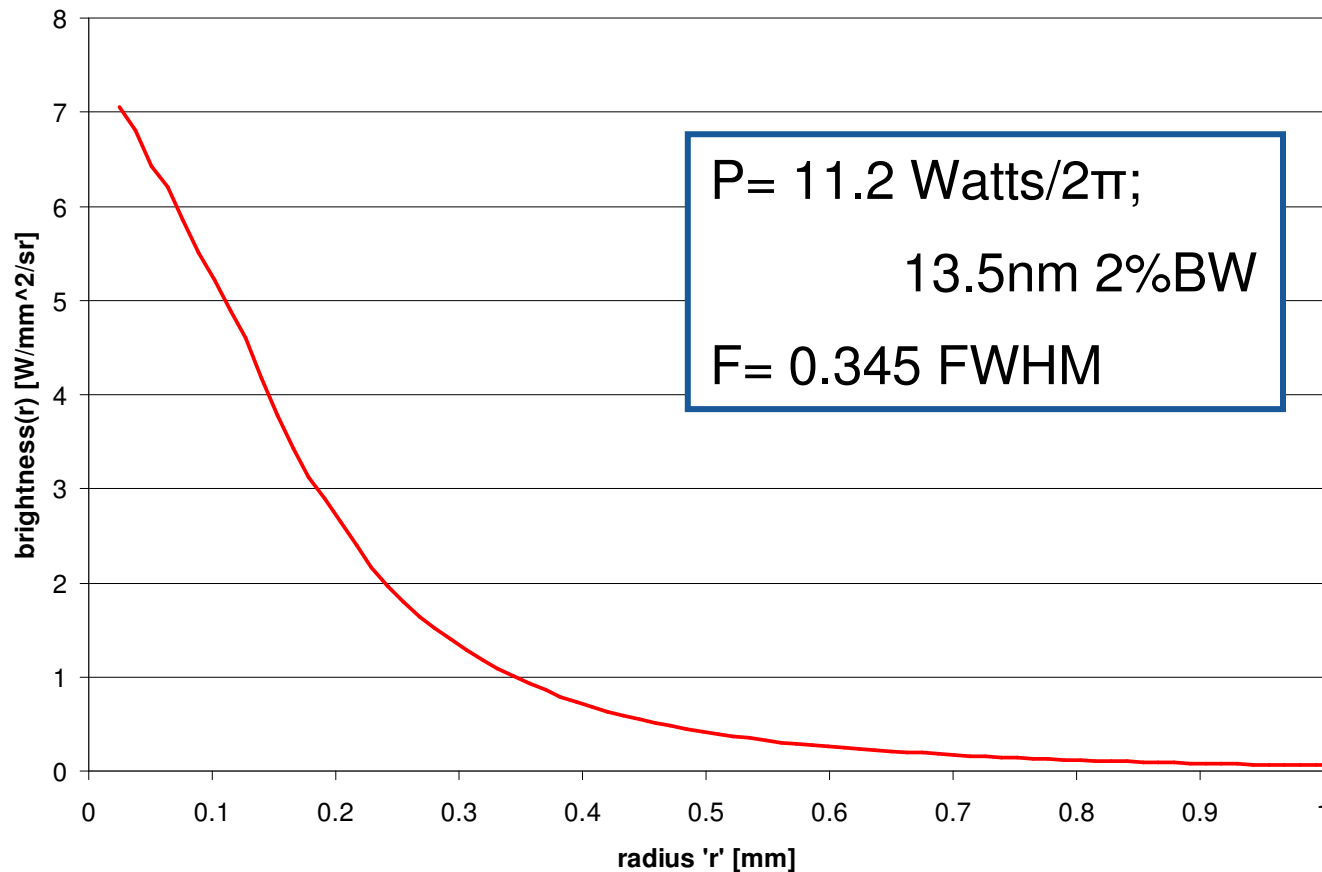


- Brightness is a function of power and radius



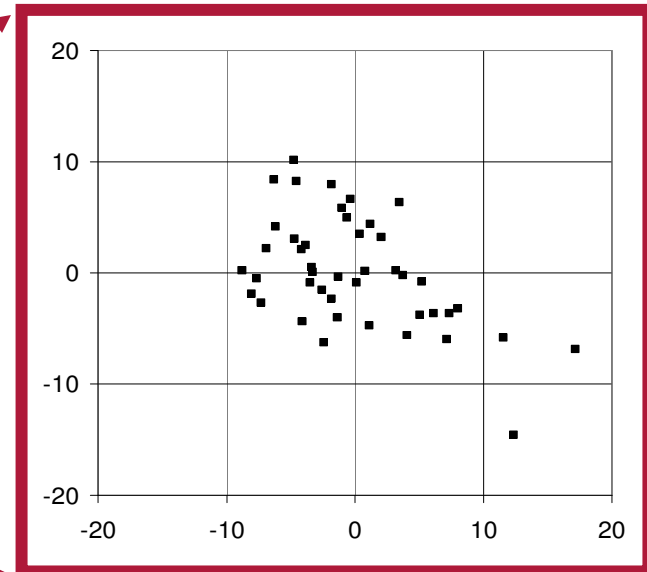
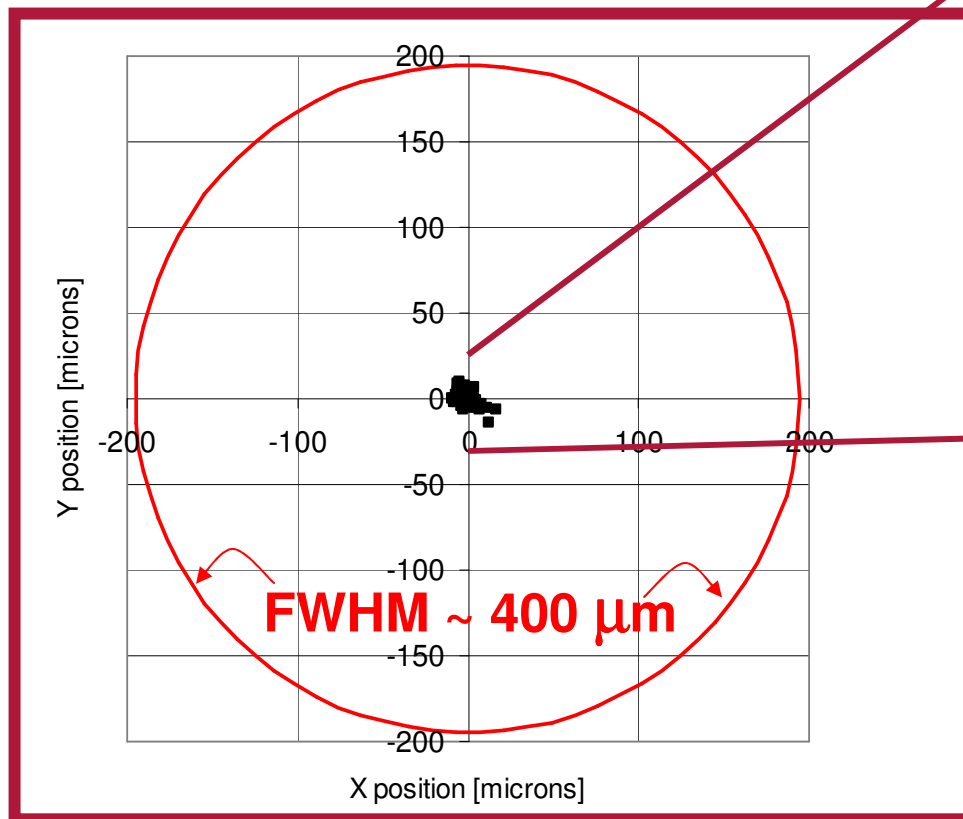
Brightness as function of radius

Standard EQ-10



Stability in EUV Plasma Position

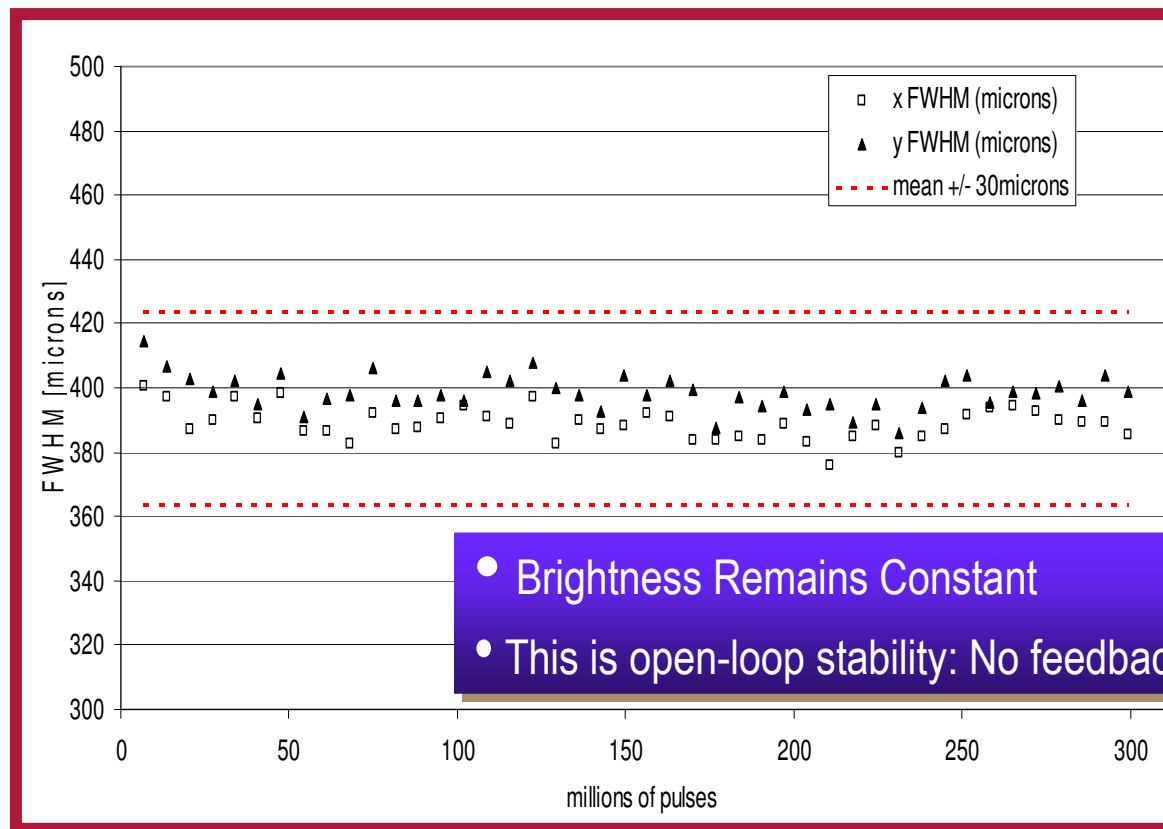
- Image recorded once an hour for over 300 million pulses (~44hours) of continuous operation. Position then extracted from images:
 - Position: $\sigma_x = 5.8 \mu\text{m}$ and $\sigma_y = 5.0 \mu\text{m}$



- Brightness remains constant
- This is open-loop stability: No feedback!

Stability in EUV Plasma Size

- Image recorded once an hour for over 300 million pulses (~44hours) of continuous operation. Size then extracted from images:
 - Size: $\sigma_{FWHMx} = 3.1 \mu m$ and $\sigma_{FWHMy} = 3.6 \mu m$

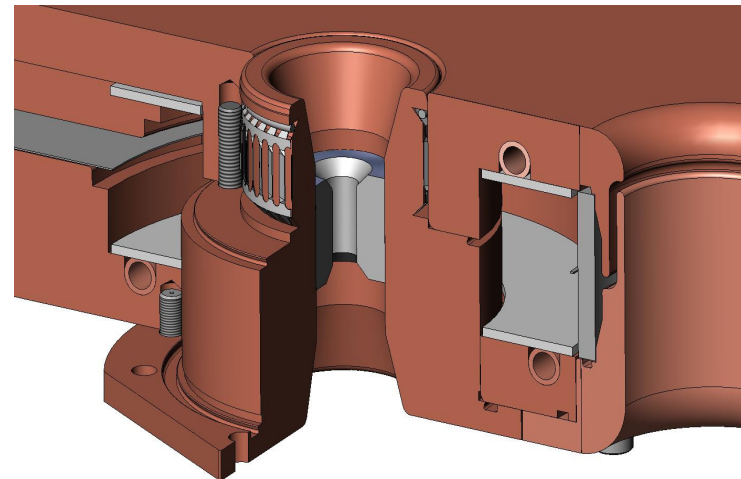
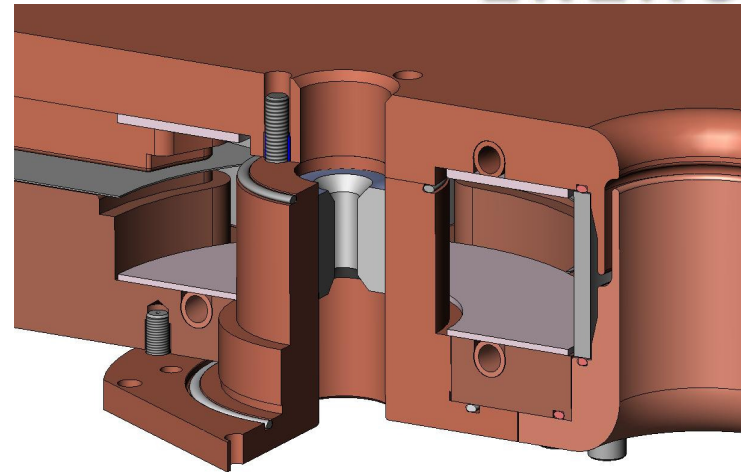


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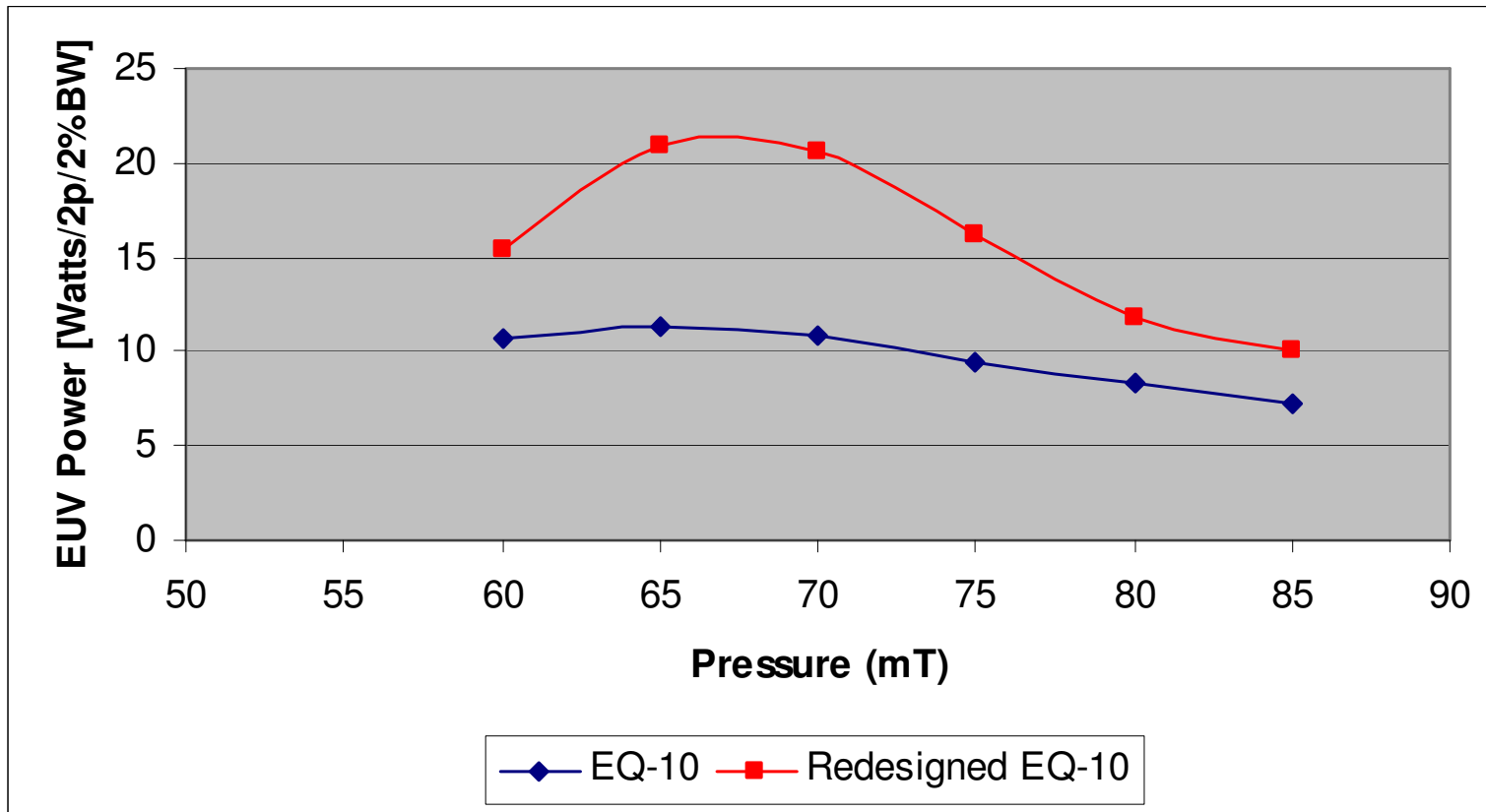
Redesigned Source

Advantages for new design

- All surfaces exposed to plasma pinch are replaced with bore exchange
- High current capacity contact insert
 - plasma erosion at contact area reduced
 - More consistent electrical contact
- Improved cooling for bore insert

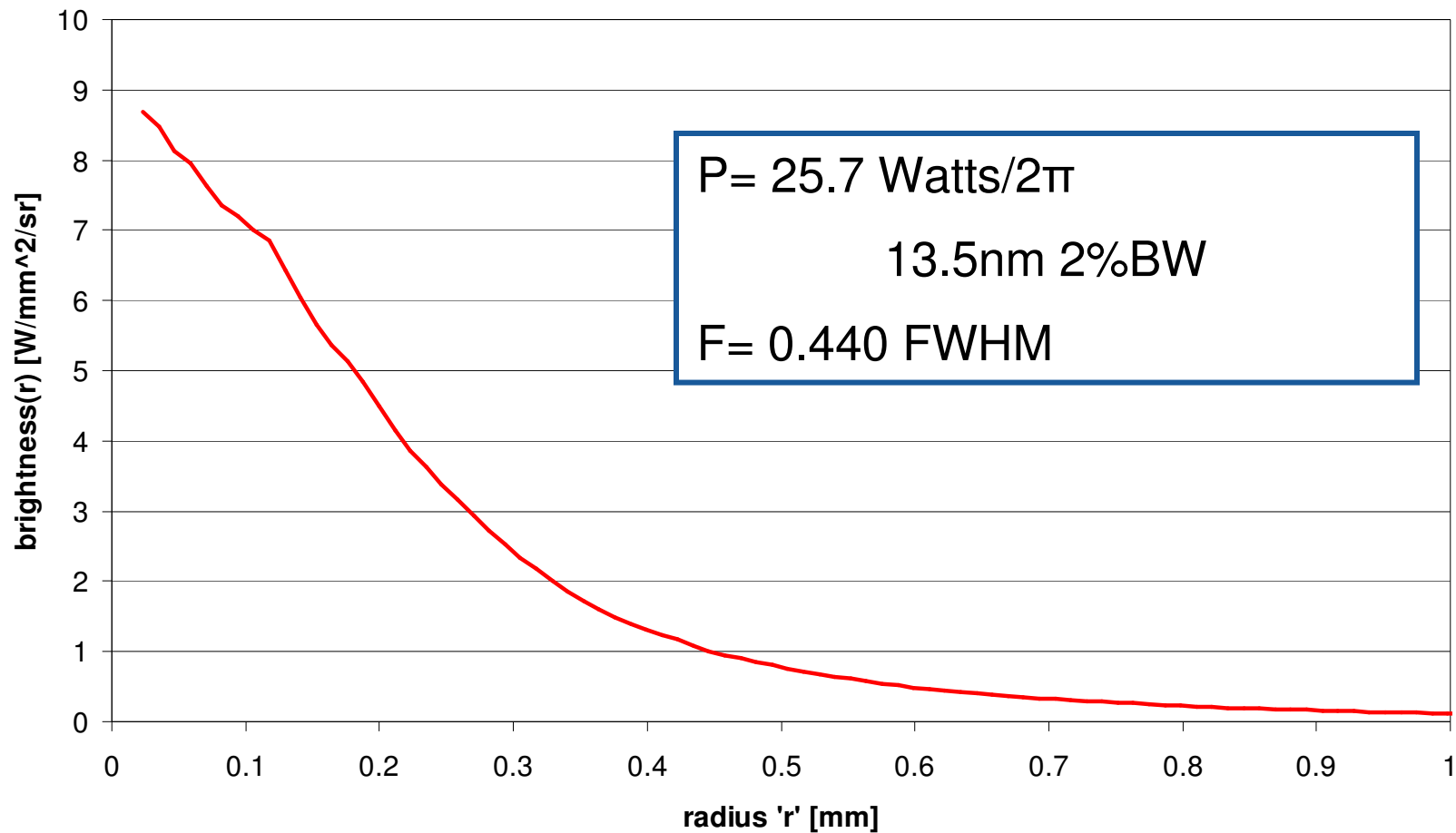


Increased Power with New Source Design



280V 1900Hz – Standard Operating Conditions

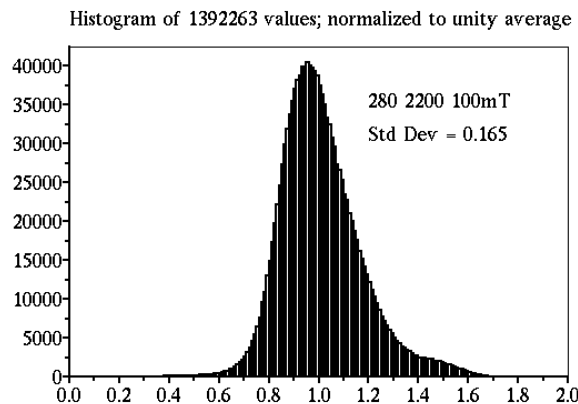
Increased Brightness New Source



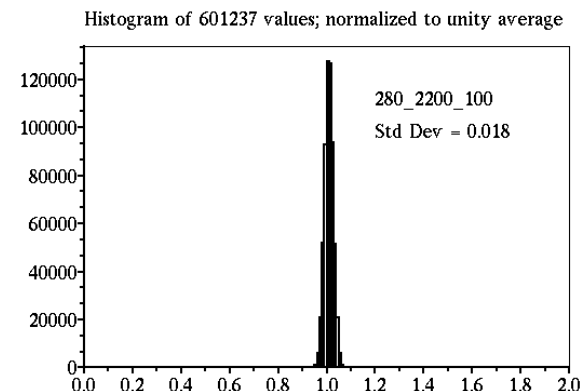
Improvements to Pulse Modulator

- The modulator was recently redesigned to improve power handling and stability.
- The redesign is to force the compression stages to a well-defined state prior to each charging cycle, thus reducing or eliminating this source of variability

•Pulse to pulse stability with Original Modulator – ~16%



•Pulse to pulse stability with redesigned Modulator ~2%



•Conditions: 280V,2200Hz,100mT

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Closing Remarks

- The Energetiq EQ-10 EUV source is a reliable and stable source of EUV photons.
- The system is being operated in the field 24/7 with consistent operation over years!
- Energetiq Sources are being used for infrastructure development globally.
- Redesign of the source offers higher power and higher brightness operation
 - Brightness of $\sim 8\text{W/mm}^2\text{-sr}$
 - $20\text{W}/2\pi$
 - Improved pulse-to-pulse stability
 - Continued excellent plasma stability

Acknowledgements

- The team at Energetiq...
- Our valued customers...
- Our excellent partners and collaborators...